Electronic Supplementary Information (ESI) for New Journal of Chemistry.

DIO: 10.1039/c4nj01319k.

Title: Development of nanocoral-like Cd(SSe) thin films via arrested precipitation technique and their application

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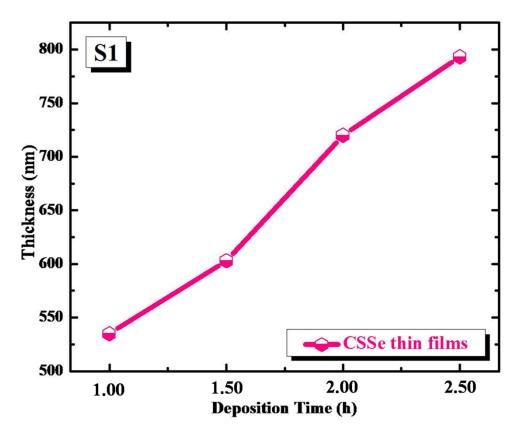


Fig. S1: Plot of variation of thickness as function of deposition time from 1.00 to 2.50h.

Thickness of as-deposited thin films increases from 535 to 793 nm with increase in deposition time and values are summarized in Table 2 (main manuscript). Variation of thickness as function of deposition time (1.00 to 2.50 h) is exposed in Fig.S1. The growth rate appreciably increases, which is up to optimized 2.50 h deposition time. This cause behind that, plentiful amounts of available Cd²⁺, S²⁻, and Se²⁻ metal ions released from bound complex state with increasing deposition time which reflects to privileged growth and thickness of thin films. At higher growth rate more metal ions goes on continuous depletion process and all metal ions are vanished from deposition solution.¹

Reference

1 K. L. Choy, Prog. Mater. Sci., 2003, 48, 57.